	Туре	L#	Hits	Search Text	DBs	Time Stamp	C o m e nt	r D ef n	ro
1	BRS	L1	4516	etch\$3 same rotat\$3 same (article or semiconductor or wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:29		!	0
2	BRS	L8	3305	1 and @pd<=20000531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:33			0
3	BRS	L15	574	(speed or revolution) same 1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:35			0
4	BRS	L22	435	15 and @pd<=20000531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:36			0
5	BRS	L29	85	22 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/20			0
6	BRS	L36	27	immers\$3 same 15	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:36			0
7	BRS	L43	20	36 and @pd<=20000531	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:36			0
8	BRS	L50	85	29 not 43.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/28 22:46			0